



NOTES

1. MATERIAL: UVFS
2. CLEAR APERTURE:  $>90\%CA$
3. SURFACE QUALITY(S1, S2): 60/40(S/D)
4. WAVEFRONT ERROR(RMS):  $\lambda/4@633\text{nm}$ (SUBSTRATE)
5. PARALLELISM(S1, S2):  $<3\text{ arcmin}$
6. ARROW POINTS TO THE FILTERING COATING
7. COATING:  
 FILTERING(S1):  $T_{\text{avg}}>90\%$ ,  $T_{\text{abs}}>85\%@470-590\text{ nm}, 45^\circ\text{ AOI}$   
 $R_{\text{avg}}>95\%$ ,  $R_{\text{abs}}>90\%@620-800\text{ nm}, 45^\circ\text{ AOI}$   
 AR COATING(S2):  $R_{\text{abs}}<2\%@470-590\text{ nm}, 45^\circ\text{ AOI}$

DRAWING PROJECTION			<b>LBTEK</b>			
	NAME	DATE				
DRAWN	LZHOU	JUL./30th/24	SHORTWAVE DICHOIC MIRROR $\phi 12.7\text{ mm} \times 3.2\text{ mm}, 605\text{ nm}$			
APPROVAL	WCHENG	JUL./30th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	0.9 g	2:1	A